



US00D420022S

United States Patent [19]

Burkhart et al.

[11] **Patent Number:** Des. 420,022
[45] **Date of Patent:** ** Feb. 1, 2000

[54] **ELECTROSTATIC CHUCK WITH
IMPROVED SPACING AND CHARGE
MIGRATION REDUCTION MASK**

[75] Inventors: **Vincent E. Burkhart; Allen Flanigan;
Steven Sansoni**, all of San Jose, Calif.

[73] Assignee: **Applied Materials, Inc.**, Santa Clara,
Calif.

[**] Term: **14 Years**

[21] Appl. No.: **29/081,238**

[22] Filed: **Dec. 24, 1997**

Related U.S. Application Data

[63] Continuation-in-part of application No. 08/639,841, May 8,
1996, Pat. No. 5,764,471.

[51] **LOC (7) Cl.** **15-09**

[52] **U.S. Cl.** **D15/140**

[58] **Field of Search** D15/140; 361/234,
361/235; 279/128; 269/8, 903

[56] **References Cited**

U.S. PATENT DOCUMENTS

5,528,451 6/1996 Su 279/128

Primary Examiner—Antoine Duval Davis
Attorney, Agent, or Firm—Thomason & Moser

[57] CLAIM

The ornamental design for an electrostatic chuck with improved spacing and charge migration reduction mask, as shown and described.

DESCRIPTION

FIG. 1 is a top view of the electrostatic chuck having the improved spacing and charge migration reduction mask;

FIG. 2 is an elevation view when looking to the right along the x-axis in FIG. 1, the view when looking to the left along the x-axis in FIG. 1 being identical to that of FIG. 2 thereof;

FIG. 3 is a detailed view of part of the surface seen in FIG. 2 thereof;

FIG. 4 is a bottom view thereof;

FIG. 5 is an elevation view when looking down along the y-axis in FIG. 1 thereof; and,

FIG. 6 is an elevation view when looking up along the y-axis in FIG. 1 thereof.

1 Claim, 2 Drawing Sheets

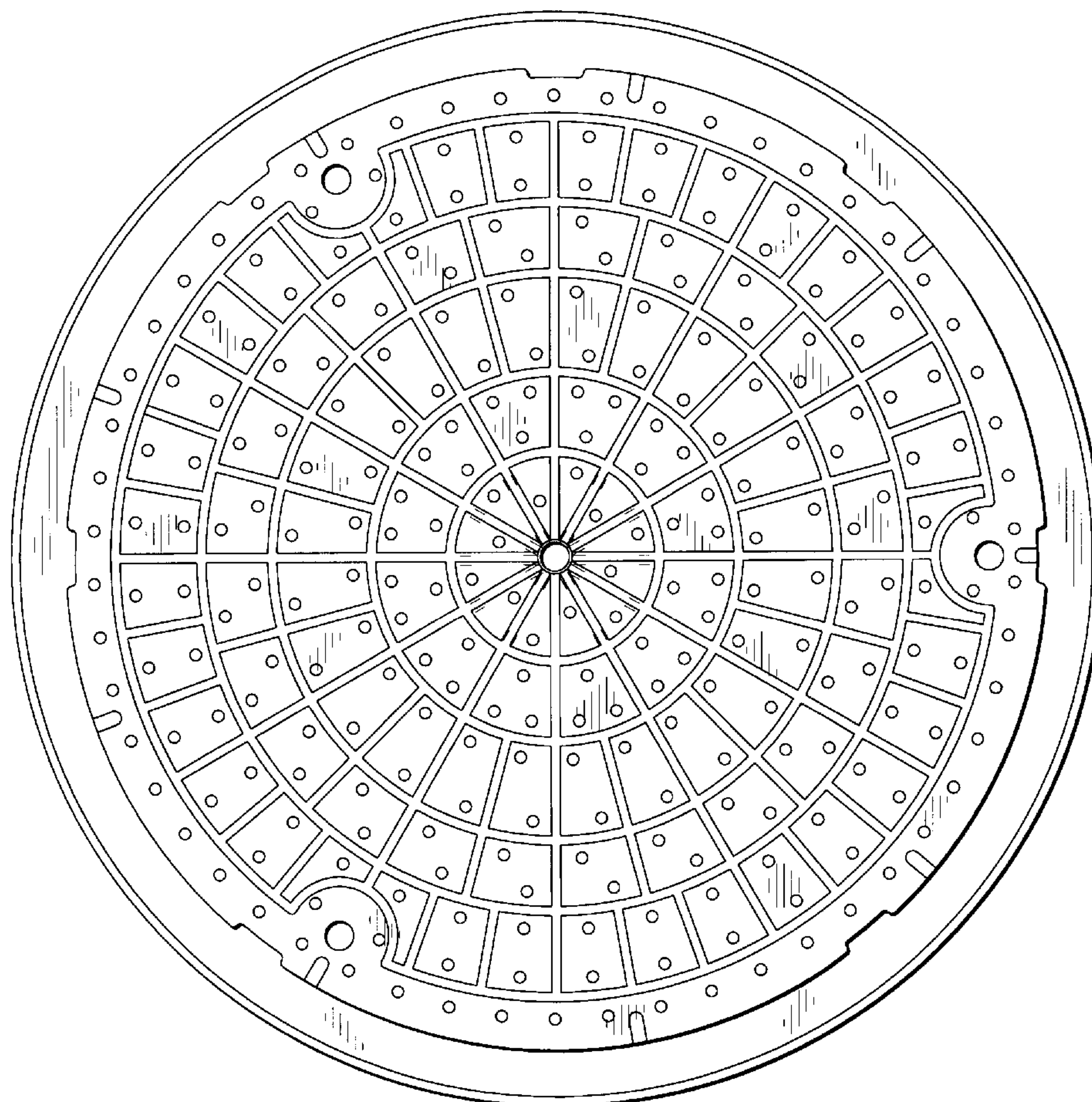


FIG. 1

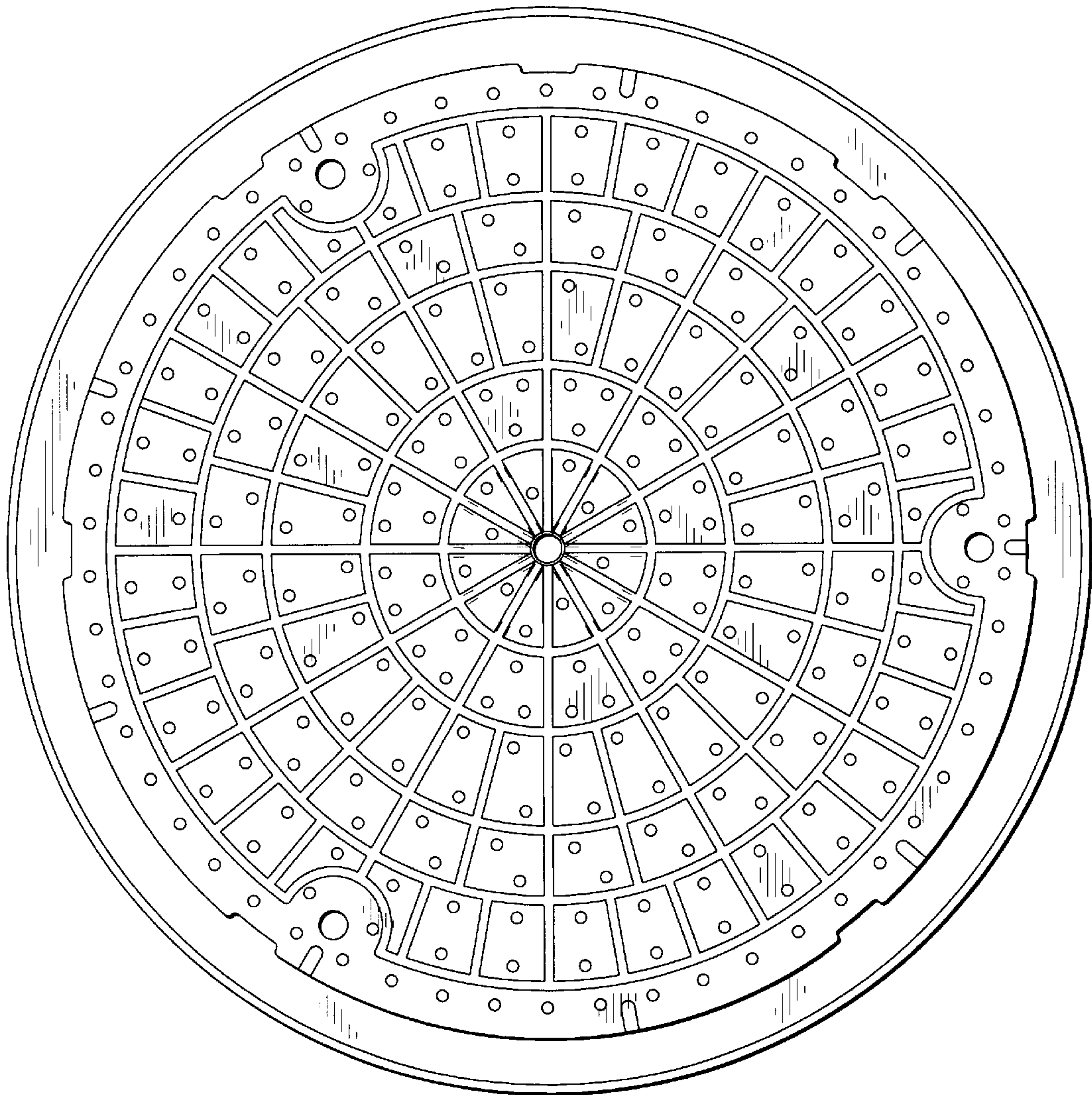


FIG. 2

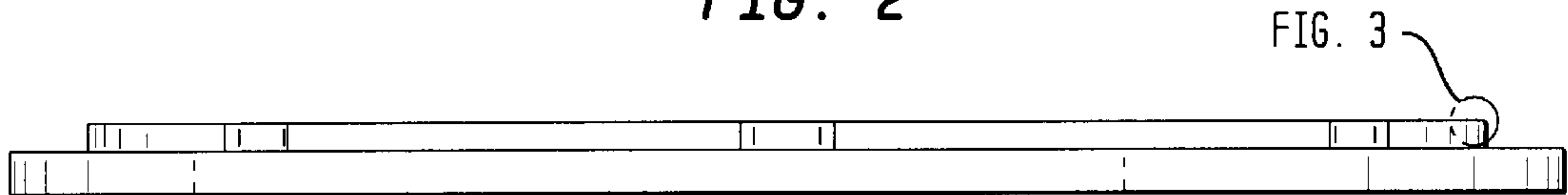


FIG. 3

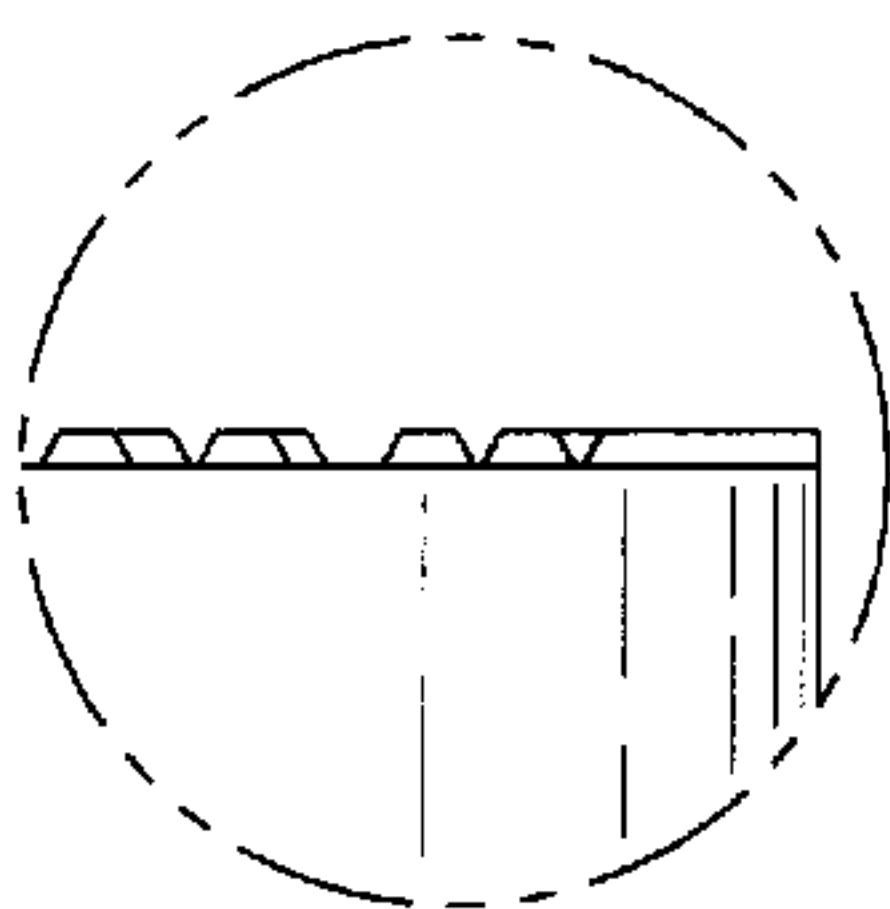


FIG. 4

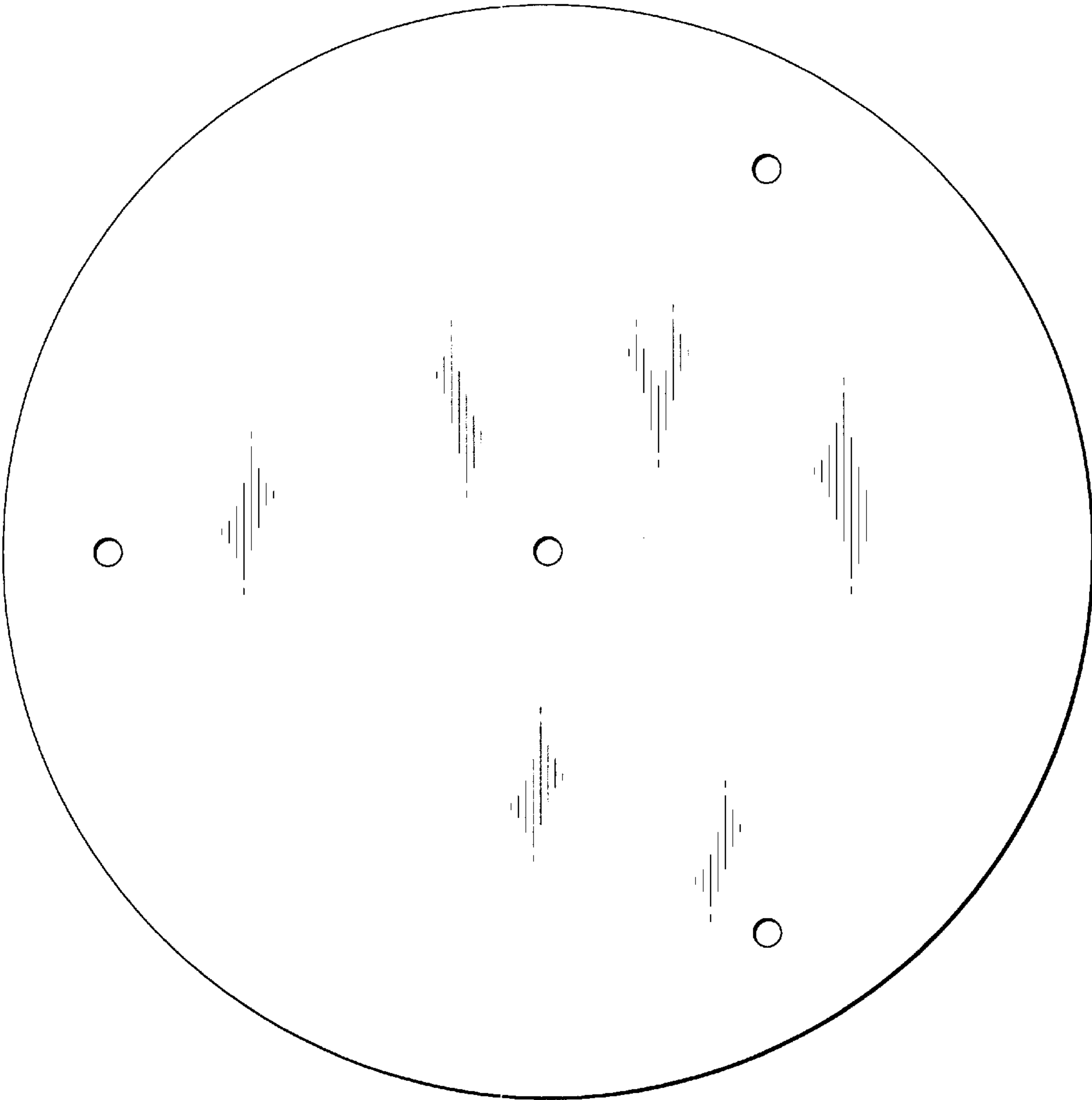


FIG. 5

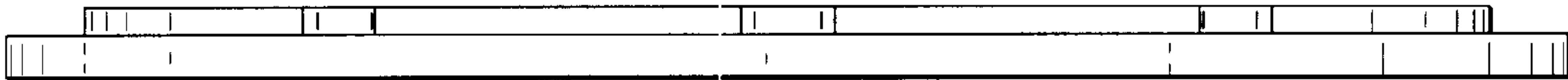


FIG. 6

